

We Claim:

1. A semiconductor structure comprising:
a monocrystalline silicon substrate;
5 an amorphous oxide material overlying the monocrystalline silicon substrate;
a monocrystalline perovskite oxide material overlying the amorphous oxide
material;
a monocrystalline compound semiconductor material overlying the
monocrystalline perovskite oxide material; and
10 an optical processing layer overlying the monocrystalline compound
semiconductor material.
2. The semiconductor structure of claim 1 wherein the optical processing layer is a
passive layer.
- 15 3. The semiconductor structure of claim 1 wherein the optical processing layer is
selected from the group consisting of a micro-Fresnel lens, a hologram lens, a grating
lens, a filter, a diffusion layer, a polarizer, a collimator, and a zone plate in combination
with an objective lens.
- 20 4. The semiconductor structure of claim 1 wherein the optical processing layer is a
active layer responsive to an active layer control signal.
5. The semiconductor structure of claim 1 wherein the optical processing layer is
25 selected from the group consisting of an electro-optic element, an electronically
switchable Bragg grating (ESBG), a switchable hologram, a switchable diffraction
grating, a switchable collimator, an application specific optical element (ASOE), a
switchable refractive element, and a liquid crystal array.

6. The semiconductor structure of claim 1 wherein the optical processing layer is a semi-active layer.
- 5 7. The semiconductor structure of claim 1 wherein the optical processing layer is a photo luminescent layer.
8. The semiconductor structure of claim 1 wherein the optical processing layer further comprises a plurality of optical processing sub-layers.
- 10 9. The semiconductor structure of claim 1 wherein the optical processing layer further comprises a feedback sensor.
10. The semiconductor structure of claim 1 wherein the monocrystalline compound
15 semiconductor material further comprises a monocrystalline compound semiconductor material having a plurality of lasers to produce photons.
11. The semiconductor structure of claim 10 wherein optical processing layer
further comprises an optical processing layer having a high beam state for collimating
20 the photons and a low beam state for redirecting and diffusing the photons.
12. The semiconductor structure of claim 10 wherein the plurality of lasers further
comprises a first laser group and a second laser group, the first laser group synchronized
with the second laser group; and wherein the optical processing layer further comprises
25 a first electro-optic element, the first electro-optic element optically connected to the
first laser group.

13. The semiconductor structure of claim 12 wherein the optical processing layer further comprises a second electro-optic element, the second electro-optic element optically connected to the second laser group.

- 5 14. A process for fabricating a semiconductor structure comprising:
providing a monocrystalline silicon substrate;
depositing a monocrystalline perovskite oxide film overlying the
monocrystalline silicon substrate, the film having a thickness less than a thickness of
the material that would result in strain-induced defects;
10 forming an amorphous oxide interface layer at an interface between the
monocrystalline perovskite oxide film and the monocrystalline silicon substrate;
epitaxially forming a monocrystalline compound semiconductor layer overlying
the monocrystalline perovskite oxide film; and
forming an optical processing layer overlying the monocrystalline compound
15 semiconductor layer.

15. The process of claim 15 wherein forming an optical processing layer further comprises film laminating the optical processing layer over the monocrystalline compound semiconductor layer.

20 16. The process of claim 15 wherein forming an optical processing layer further comprises printing the optical processing layer over the monocrystalline compound semiconductor layer.

25 17. The process of claim 15 wherein forming an optical processing layer further comprises spin coating the optical processing layer over the monocrystalline compound semiconductor layer